



PATENT

Atty. Dkt. No. AMAT/3032.C6/DSM/LOW K/JW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Cheung, et al.

Serial No.: 10/648,616

Confirmation No.: 4378

Filed: August 26, 2003

For: Plasma Processes for
Depositing Low Dielectric
Constant Films

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Group Art Unit: 2818

Examiner: Thao P. Le

MAIL STOP AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

CERTIFIED OF MAILING 37 CFR 1.8	
I hereby certify that this correspondence is being deposited on <u>3/29, 2005</u> with the United States Postal Service as First Class Mail in an envelope addressed to: Mail Stop Amendment, Commissioner for Patents, P.O. BOX 1450, Alexandria, VA 22313-1450.	
<u>3/29/05</u> Date	<u>[Signature]</u> Signature

RESPONSE TO OFFICE ACTION DATED FEBRUARY 1, 2005

In response to the Office Action dated February 1, 2005, having a shortened statutory period for response set to expire on May 1, 2005, please enter this response and reconsider the claims pending in the application for reasons discussed below. The Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/AMAT/3032.C6/KMT for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Specification begin on page 2 of this paper. **Amendments to the Claims** are reflected in the listing of claims which begins on page 9 of this paper. **Remarks** begin on page 13 of this paper.